ARIZONA STATE UNIVERSITY

AUG 2000

CONFIDENTIAL

DISCLOSURE AND RECORD OF INVENTION FORM

Once completed, this f rm is considered proprietary & confidential by the Arizona Board of Regents.

Arizona State University
Office of Technology Collaborations & Dicensing

ASU Disclosure # MI-008

1. Short descriptive title of the invention.

PROGRAMMABLE METALLIZATION CELL WITH FLOATING-

CIRCUMSTANCES OF THE INVENTION

2. List the funding source(s) for the project under which this invention was made. Identify by contract or grant number as well as Area/Org No. and name of the Principal Investigator.

EXONO TECHNOLOGIAS	TC600-1048	DW7 0099	M.N.KOZICKI

- 3. For any "Inventor" named on page 3 who is not employed full-time by Arizona State University, please identify their employers, the percent of salary time funded by such other employers, the nature of the other employment (such as research, teaching or clinical duties), AND WHERE THEIR INVENTIVE CONTRIBUTION WAS MADE.
 - 4. When did you first conceive this invention?



- 5. What is the date of the first written record (notebook, letter, proposal, drawing, etc.) of this invention? Identify the document, page numbers involved, and location of the document (please attach copies, if possible).

 LABORATORY NOTEBOOK, DR. MICHAEL KOZICKI (6/2/00)
- 6. When did you first successfully test this invention?

C/23/00

7. Identify any references, patent applications, or other publications of which you are aware and which you believe to be pertinent to this invention. Please attach a copy of each of these references, if available.

SEE PATENT TREE

8. If any proprietary material (e.g., cell line, antibody, plasmid, computer software, or chemical compound) obtained from utside y ur lab ratory was used t develop this invention under a written transfer agreement (other than an rmal purchasing agreement), please attach a c py of that agreement if available. If it is n t available, please let us kn w if the document exists, and, possibly, where it may be.

DISCLOSURE & PUBLICATION PLANS (EXTREMELY IMPORTANT)

Public disclosure affects patent rights - Please answer diligently

	under what circumstances, and to whom. NO PUBLIC DISCLOSURE					
a.	orally:					
b.	in writing:					
c.	by actual use, demonstration, or posters:					
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THIS INVENTION DISCLOSURE W. I NOT BE PROCESSED UNLESS THIS PORTION IS FILLED OUT COMPLETELY

13. Signatures, Names and addresses of Inventors

The undersigned agree to comply with ABOR policies on intellectual property and to execute suitable assignments of title if and when asked to do so.

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Lower oxidizable layer – e.g. silver (required only if lower electrode is non-silver) Solid solution 1 – e.g. silver in germanium selenide Floating electrode – e.g. tungsten or other indifferent conductor Solid solution 2 – e.g. silver in germanium selenide Upper oxidizable layer – e.g. silver (required only if upper electrode is non-silver) Upper electrode – e.g. silver or indifferent conductor

The horizontal variant would involve the same electrode options but deposited in a coplanar fashion on the surface of the solid solution such that the floating electrode is placed between the other two (connected) electrodes.

Basis of patent application and claims:

- 1. Use of a floating electrode in a PMC device or a derivative of such.
- 2. Use of oxidizable or indifferent electrode in this context.
- 3. Enhancement of data storage capabilty, allowing four easily read states (two bits) to be programmed in each cell of a PMC-like device.
- 4. Programming of the cell using polarity and current sequences.
- 5. Use of the device as a programmable anti-fuse element.
- 6. Formation of both horizontal and vertical variants of the device.

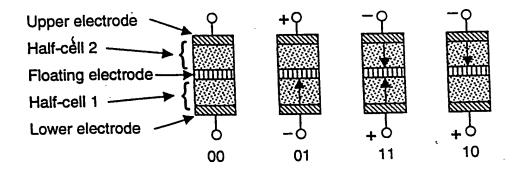
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Effective 10/1/98

Programmable Metallization Cell with FI ating EI ctrode Multi-state programmable microelectronic device

The Floating Electrode Programmable Metallization Cell (FEPMC) uses an unconnected (floating) electrode between layers of a solid solution. The FEPMC operates in a similar fashion to the two electrode (asymmetric) PMC device in that an electrodeposit is made to form on or in a solid solution by the application of a small potential. The low resistance metallic electrodeposit shorts out the high resistivity glass and can be subsequently removed by the application of a reverse bias. This is how information is stored in the PMC device. The unique structure of the FEPMC allows four distinct and easily programmed states, which can represent two bits of binary information, to be stored in a single device.

The FEPMC structure essentially has five layers; lower electrode, solid solution 1, floating electrode, solid solution 2, and upper electrode. (Note that although this description pertains to a vertical device, a horizontal structure is also possible with all three electrodes being deposited on the surface of a thin layer of the solid solution.) If the floating electrode is the same as the metal in solution and the lower and upper electrodes are indifferent, or *vice-versa*, the entire structure may be thought of as two back-to-back PMC devices with a common electrode. Each "half-cell" is a PMC device in its own right but the common electrode is only supplied with electrons or ions via the solid solution layers and not by any other external connection. The full structure is shown schematically in the figure below.



Considering first the case of a structure with an oxidizable floating electrode, e.g., silver. In the unprogrammed state, the half cells have geometry and solution dependent impedances of Z_1 for half-cell 1 and Z_2 for half-cell 2. Typically, the solution layer thicknesses will be chosen so that Z_1 and Z_2 are distinctly different. The overall impedance of the FEPMC structure will be given by Z_1 in series with Z_2 and this may be used to represent state 00. If a voltage is applied such that the upper electrode is positive with respect to the lower electrode and the magnitude is above that necessary to promote electrodeposition in half-cell 1, an electrodeposit will form from the lower electrode to the floating electrode as

shown by the arrow in the figure. Note that an electrodeposit will not grow in half-cell 2 as it is "reverse biased" and so will not support electrodeposition. The electrodeposit will change the impedance of half-cell 1 to Z_1 , changing the overall impedance of the FEPMC and producing a value which may represent state 01. The current or charge limit will set the magnitude of the change and should be chosen sufficiently low so that it is possible to subsequently erase the electrodeposit with a reasonable current.

If the polarity is now reversed (with a similar low current level), most of the applied bias will be dropped across the high resistance solution of half-cell 2 rather than across half-cell 1, and so an electrodeposit will form from the top electrode to the floating electrode without dissolving the connection in half-cell 1, as shown in the figure. The impedance of half-cell 2 now becomes Z_2 ' and the overall impedance is Z_1 ' in series with Z_2 '. This device impedance can be used to represent state 11.

Once both half-cells are shorted, either electrodeposit can be dissolved by applying a sufficient (reverse) bias across the appropriate half-cell. However, if the upper electrode is once again made negative with respect to the lower but using a higher current limit which allows sufficient reverse bias across half-cell 1, only this cell will be erased (see figure). Half-cell 1 will therefore return to Z_1 and the overall device impedance will be Z_1 in series with Z_2 , representing state 10. The entire four state sequence is summarized in the table below.

Seq#	Polarity	Current.limit:	Z half-cell:1	Zhalf-cell'2	State/value
1	Sub-threshold	Zero	Z ₁	Z ₂	00
2	Upper + Lower -	Low	Z ₁ '	Z_2	01
3	Upper - Lower +	Low	Z ₁ '	Z ₂ '	11
4	Upper - Lower +	High	Z ₁	Z ₂ '	10

It is possible to return to state 11 from state 10 simply by applying a low current limit bias to regrow the electrodeposit in half-cell 1 (upper +, lower -). From state 11, dissolving the electrodeposit in half-cell 2 by applying a high current limit bias such that the upper electrode is again positive with respect to the lower will take the device to state 01. Finally, if state 00 is now to be attained, a short current pulse must be applied to thermally dissolve the electrodeposit in half-cell 1. This can be done with the same polarity as the half-cell 1 write but with a current limit which is high enough to cause localized heating of the electrodeposit. This will increase the metal concentration in the half-cell but this excess metal can be removed electrically from the cell by plating it back onto the floating electrode (this will happen when half-cell 2 is written to, i.e., when the upper electrode is negative with respect to the lower). This sequence is summarized in the table below.

Seq #	Polarity	Current limit	Z half-cell 1	Z half-cell 2	State/value
4	Existing state	•	Z ₁	Z ₂ '	10
5	Upper + Lower -	Low	Z ₁ '	Z ₂ '	11
- 6	Upper + Lower -	High	Z ₁ '	Z ₂	01
7	Upper + Lower -	Thermal	Z ₁	Z ₂	00

Note that other sequences are possible (as are other definitions of the various states represented by the half-cell impedances). For example, it is possible to go from state 00 to either state 01 or state 10, depending on the write polarity chosen. Similarly, it is possible to go from state 11 to either state 10 or state 01. It is also possible to go from state 11 to state 00 by the application of a current pulse (in either direction) which is high and short enough to thermally dissolve the electrodeposits in both half-cells simultaneously.

In addition to storing information in digital form, the FEPMC can also be used as a noise-tolerant low energy anti-fuse element for use in field programmable gate arrays (FPGAs) and field configurable circuits and systems. Most physical anti-fuse technologies require large currents and voltages to make a permanent connection. The need for such high energy state-switching stimuli is generally considered to be somewhat beneficial as this reduces the likelihood of the anti-fuse accidentally forming a connection in electrically noisy situations. However, the use of high voltages and large currents on chip represent a significant problem as all components in the programming circuits have to be sized accordingly and the high energy consumption reduces battery life in portable systems.

The FEPMC represents a low energy anti-fuse solution which is relatively noise immune. The device can only be closed (fully shorted to the lowest impedance state) if a pulse of one polarity is followed by one of the opposite polarity. This eliminates the likelihood of switching due to unipolar voltage spikes, which are common in digital and mixed signal integrated circuits.

Two vertical configurations of the FEPMC are possible, both being formed by multi-layer deposition. Note that the vertical FEPMC can be fabricated so that it is entirely contained within a via in a dielectric layer. For an oxidizable floating electrode, the layer sequence would be as follows:

Lower electrode – e.g. tungsten or other indifferent conductor Solid solution 1 – e.g. silver in germanium selenide Floating electrode – e.g. silver Solid solution 2 – e.g. silver in germanium selenide Upper electrode – e.g. tungsten or other indifferent conductor

For a non-oxidizable floating electrode, the layer sequence would be as follows:

Lower electrode - e.g. silver or an indifferent conductor

Lower oxidizable layer – e.g. silver (required only if lower electrode is non-silver) Solid solution 1 – e.g. silver in germanium selenide Floating electrode – e.g. tungsten or other indifferent conductor Solid solution 2 – e.g. silver in germanium selenide Upper oxidizable layer – e.g. silver (required only if upper electrode is non-silver) Upper electrode – e.g. silver or indifferent conductor

The horizontal variant would involve the same electrode options but deposited in a coplanar fashion on the surface of the solid solution such that the floating electrode is placed between the other two (connected) electrodes.

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